

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| In re Application of: | | on of: |) <u>ATTENTION AFTER FINAL PRACTICE</u>) EXPEDITED PROCESSING | |
|-----------------------|---------|---------------------|--|--------------------------------|
| | Naoshi | ADACHI et al. |) <u>===</u> | |
| | | |) | Art Unit: 2826 |
| Serial 1 | No.: | 10/750,883 |) | |
| | | |) | Examiner: Williams, Alexander |
| Filed: | January | 5, 2004 |) | |
| For: | HEAT | TREATMENT JIG FOR S | EMICON | DUCTOR SUBSTRATE AND METHOD OF |

AMENDMENT

Commissioner of Patents P.O. Box 1450 Alexandria, VA 22313-1450

HEAT TREATING SEMICONDUCTOR SUBSTRATE

Sir:

In response to the Final Office Action dated March 13, 2007, Applicants request reconsideration of the final rejection of the claims. Please revise the claims as follows: